

1/3

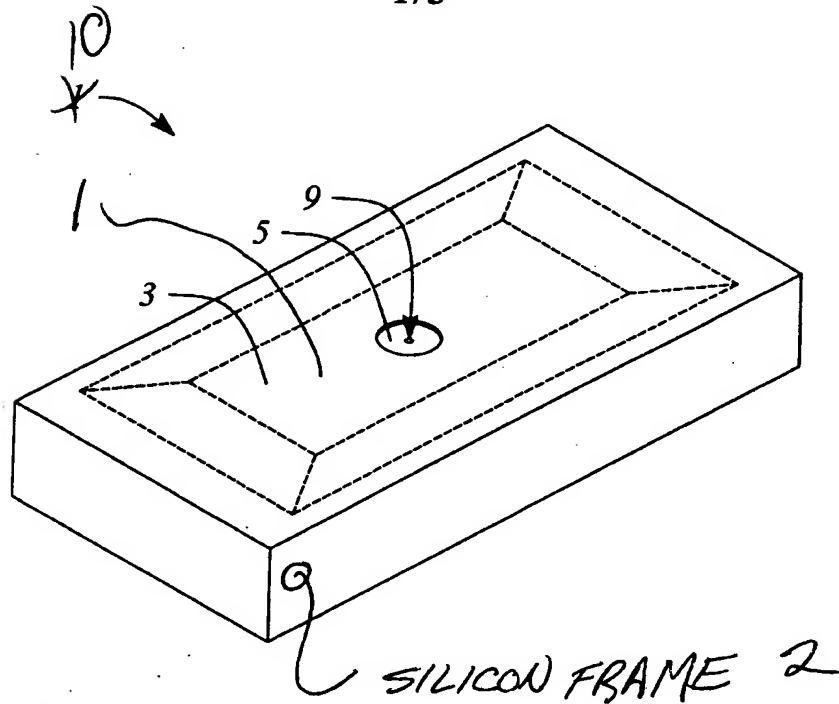


FIG. 1

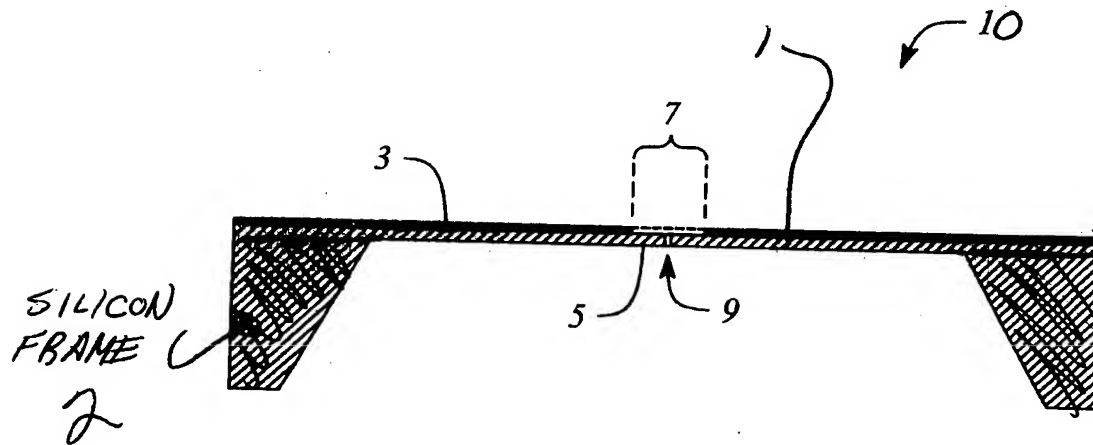
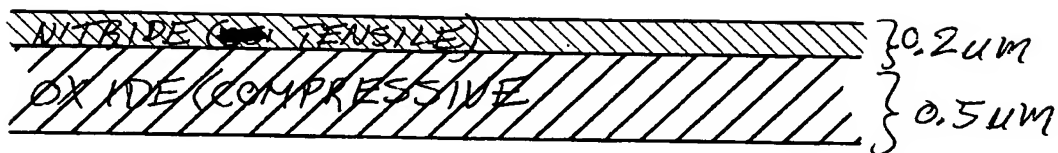
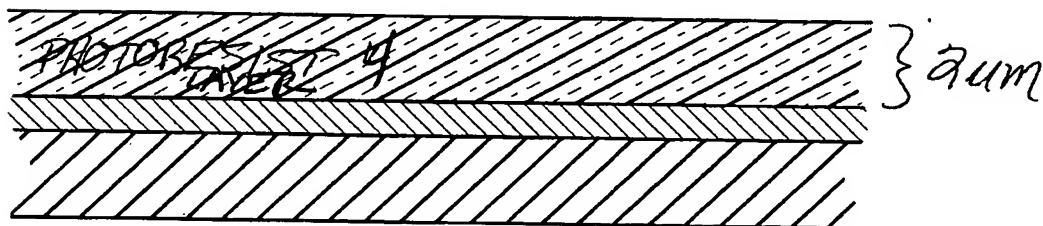


FIG. 2

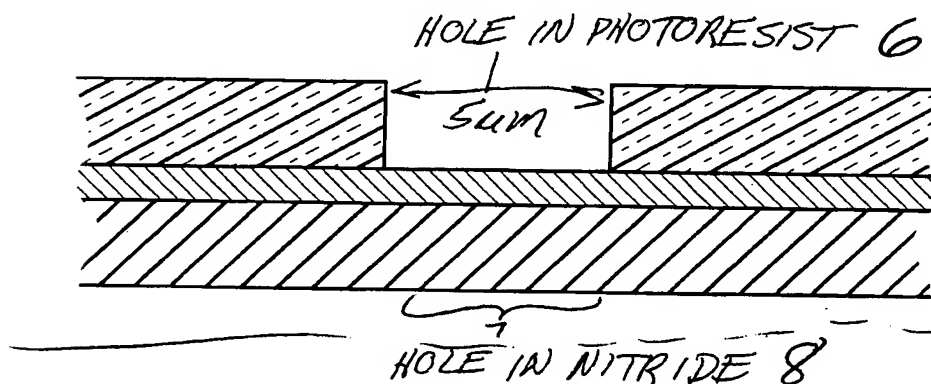
3 A



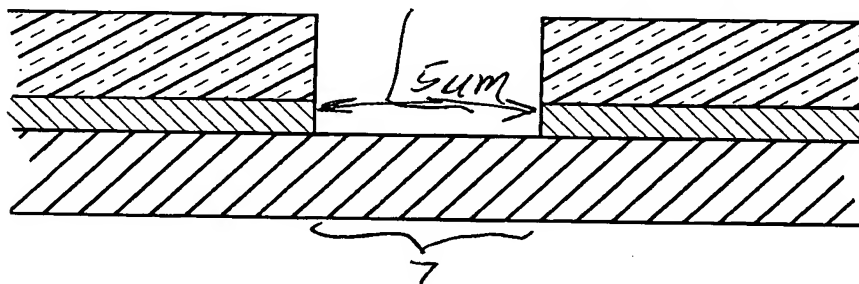
3 B



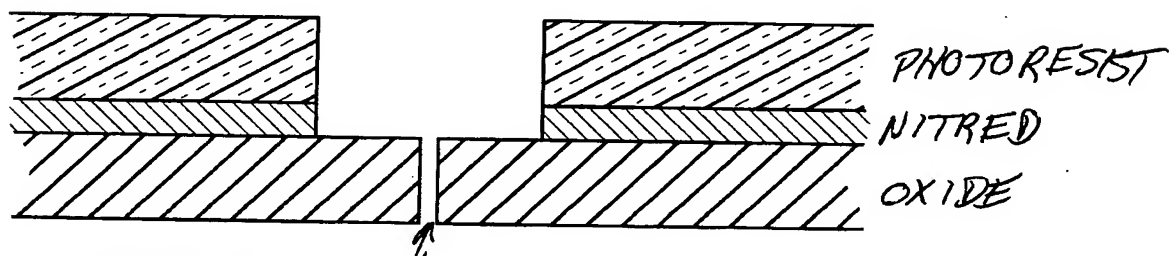
3 C



3 D



3 E

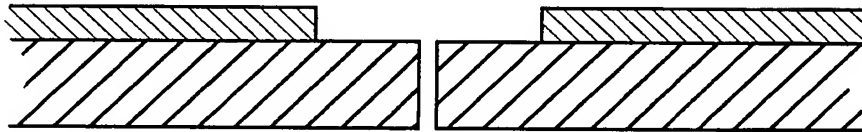


NANOPORE IN OXIDE BY F.I.B. TO FORM
 HOLE < 100 nm IN DIAMETER FOLLOWED BY
 ION BEAM SCULPTING IN ARGON TO CLOSE HOLE
 DOWN TO NANOPORE DIMENSIONS

REMOVE PHOTORESIST



3F



Note: The photoresist can be ^{optionally} removed before the F.I.B. hole is formed.